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(54) Title: COLOR FILTER BLACK MATRIX RESIST COMPOSITION AND CARBON BLACK DISPERSION COMPOSITION USED FOR THE COMPOSITION

(57) Abstract: The present invention provides a carbon black dispersion composition for a color filter black matrix resist composition, containing (A) a carbon black having specified physical properties (average primary particle diameter, concentration of surface carboxyl groups), (B) a copolymer having an amino group and/or its quaternary ammonium salt, and (C) an organic solvent, and a color filter black matrix resist composition that contains the above-mentioned dispersion composition, (D) a binder resin having a carboxyl group, (E) an ethylenically unsaturated monomer, (F) a photopolymerization initiator, and (G) specified multifunctional thiol compound and can easily form a thin film or pattern having high light-shielding property by photolithographic method pattern, has excellent storage stability, and exhibits sufficient sensitivity and resolution.

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